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C23C 14/34**C22C 5/06****G11B 7/24****G11B 7/26**(21)Application number : **2001-138674**(71)Applicant : **ISHIFUKU METAL IND CO LTD**(22)Date of filing : **09.05.2001**(72)Inventor : **HASEGAWA KOICHI
ISHII NOBUO
ASAKI TOMOMI****(54) SPUTTERING TARGET MATERIAL**

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a sputtering target material composed of Ag alloy and having high reflectivity and excellent sulfidation resistance.

SOLUTION: The sputtering target material is composed of the Ag alloy which is prepared by adding specific small amounts of metal component (A) selected from Ge, Ga and Sb, specific small amounts of metal component (B) selected from Au, Pd and Pt, and, if necessary, a small amounts of Cu to Ag and carrying out alloying.

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